

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number.

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**
(Not for submission under 37 CFR 1.99)

Application Number	10518060
Filing Date	2005-06-09
First Named Inventor	Lutz Lehmann
Art Unit	1712
Examiner Name	Kua Liang Peng
Attorney Docket Number	H26787.68596 US - 4780

U.S. PATENTS

Examiner Initial*	Cite No	Patent Number	Kind Code ¹	Issue Date	Name of Patentee or Applicant of cited Document	Pages, Columns, Lines where Relevant Passages or Relevant Figures Appear
	1	3884702		1975-05-20	Unitika, Ltd.	
	2	4299938		1981-11-10	Ciba-Geigy Corporation	
	3	4349609		1982-09-14	Fujitsu Limited	
	4	4430153		1984-02-07	International Business Machines	
	5	4587138		1986-05-06	Intel Corporation	
	6	4863827		1989-09-05	American Hoechst Corporation	
	7	4910122		1999-03-20	Brewer Science, Inc.	
	8	4935583		1990-06-19	Kyle, James C.	

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**
(Not for submission under 37 CFR 1.99)

Application Number	10518060
Filing Date	2005-06-09
First Named Inventor	Lutz Lehmann
Art Unit	1712
Examiner Name	Kua Liang Peng
Attorney Docket Number	H26787.68596 US - 4780

9	4935320		1990-06-19	Ciba-Geigy Corporation	
10	4950583		1990-08-21	Brewer Science Inc.	
11	5100503		1992-03-31	NCR Corporation	
12	5126289		1992-06-30	AT&T Bell Laboratories	
13	5403680		1995-04-04	Osaka Gas Company, Ltd.	
14	5759625		1998-06-02	E.I. du Pont de Nemours and Company	
15	7014982	B1	2006-03-21	Shipley Company, L.L.C.	
16	90008360			Shipley Company, L.L.C.	
17	5851738		1998-12-22	Shipley Company, L.L.C.	
18	6165697		2000-12-26	Shipley Company, L.L.C.	
19	6451503	B1	2002-09-17	Shipley Company, L.L.C.	

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**
(Not for submission under 37 CFR 1.99)

Application Number	10518060
Filing Date	2005-06-09
First Named Inventor	Lutz Lehmann
Art Unit	1712
Examiner Name	Kua Liang Peng
Attorney Docket Number	H26787.68596 US - 4780

20	6472128	B2	2002-10-29	Shipley Company, L.L.C.	
21	6528235	B2	2003-02-04	Shipley Company, L.L.C.	
22	5674648	A	1997-10-07	Brewer et al.	
23	4191571		1980-03-04	Nonogaki et al.	

If you wish to add additional U.S. Patent citation information please click the Add button.

U.S. PATENT APPLICATION PUBLICATIONS

Examiner Initial*	Cite No	Publication Number	Kind Code ¹	Publication Date	Name of Patentee or Applicant of cited Document	Pages, Columns, Lines where Relevant Passages or Relevant Figures Appear
	1	20060110682	A1	2006-05-25	Shipley Company, L.L.C.	
	2	20060155594	A1	2006-07-13	Jess Almeida, et al.	

If you wish to add additional U.S. Published Application citation information please click the Add button.

FOREIGN PATENT DOCUMENTS

Examiner Initial*	Cite No	Foreign Document Number ³	Country Code ² j	Kind Code ⁴	Publication Date	Name of Patentee or Applicant of cited Document	Pages, Columns, Lines where Relevant Passages or Relevant Figures Appear	T ⁵
	1							<input type="checkbox"/>

If you wish to add additional Foreign Patent Document citation information please click the Add button

NON-PATENT LITERATURE DOCUMENTS

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**
(Not for submission under 37 CFR 1.99)

Application Number	10518060
Filing Date	2005-06-09
First Named Inventor	Lutz Lehmann
Art Unit	1712
Examiner Name	Kua Liang Peng
Attorney Docket Number	H26787.68596 US - 4780

Examiner Initials*	Cite No	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc), date, pages(s), volume-issue number(s), publisher, city and/or country where published.	T ⁵
	1	Crivello et al., J. Polym. Sci.: Polym. Chem. 21 (1983), 97-109.	<input type="checkbox"/>
	2	Degussa, "Silanes for Adhesives and Sealants," 18-19, available at www.dynasylan.com.	<input type="checkbox"/>
	3	Lamola, A. et al., "Chemically Amplified Resists," Solid State Technology, 53-60 (August 1991).	<input type="checkbox"/>
	4	Y.-C. Lin et al., "Some Aspects of Anti-Reflective Coating for Optical Lithography," Advances in Resist Technology and Processing, Proc., SPIE vol. 469, 30-37 (1984).	<input type="checkbox"/>
	5	McKean et al., "Characterization of a Novolac-Based Three-Component Deep-UV Resist," Chem. Mater. (1990) 2, 619-624.	<input type="checkbox"/>
	6	Nalamasu et al., "Development of a Chemically Amplified Positive (CAMP) Resist Material for Single Layer Deep-UV Lithography," Advances in Resist Technology and Processing VII, SPIE 1262, 32-41 (1990).	<input type="checkbox"/>
	7	Silverstein et al., "Spectrometric Identification of Organic Compounds," 4th Ed. John Wiley & Sons 1991, 309-311.	<input type="checkbox"/>
	8	Willson, C.G., "Organic Resist Materials - Theory and Chemistry," Introduction to Microlithography, American Chemical Society, 87-159 (1983).	<input type="checkbox"/>
	9	Hawley's Condensed Chemical Dictionary, 11th ed., 85-86.	<input type="checkbox"/>
	10	"HD Micro Puts Out Positive Polyamide," Electronic News, June 19, 2000.	<input type="checkbox"/>

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**
(Not for submission under 37 CFR 1.99)

Application Number	10518060
Filing Date	2005-06-09
First Named Inventor	Lutz Lehmann
Art Unit	1712
Examiner Name	Kua Liang Peng
Attorney Docket Number	H26787.68596 US - 4780

11	Jaskot et al., Toxicological Sciences, 22(1): 103-112 (1994).	<input type="checkbox"/>
12	Y.-C. Lin et al., "Some Aspects of Anti-Reflective Coating for Optical Lithography," Advances in Resist Technology and Processing, Proc., SPIE vol. 469, 30-37 (1984).	<input type="checkbox"/>
13	Brewer, T. et al., "The Reduction of the Standing Wave Effect in Positive Photoresists," Jour. Appl. Photogr. Eng., Vol. 7, no. 6, 184-186 (Dec. 1981).	<input type="checkbox"/>
14	Yusuke Izumi et al., "Hydrosilylation of Carbonyl Compounds Catalyzed by Solid Acids and Bases," Tetrahedron Letters, Vol. 32, No. 36, pp 4744 (1991).	<input type="checkbox"/>

If you wish to add additional non-patent literature document citation information please click the Add button

EXAMINER SIGNATURE

Examiner Signature	Date Considered
--------------------	-----------------

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through a citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ See Kind Codes of USPTO Patent Documents at www.USPTO.GOV or MPEP 901.04. ² Enter office that issued the document, by the two-letter code (WIPO Standard ST.3). ³ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁴ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. ⁵ Applicant is to place a check mark here if English language translation is attached.